

UNITED STATES PATENT AND TRADEMARK OFFICE

BEFORE THE PATENT TRIAL AND APPEAL BOARD

MICRON TECHNOLOGY, INC.,
INTEL CORPORATION, AND
GLOBALFOUNDRIES U.S., INC.,

Petitioners

v.

DANIEL L. FLAMM,

Patent Owner

Case IPR No. Unassigned
U.S. Patent No. 6,017,221
Issued: January 25, 2000
Named Inventor: Daniel L. Flamm

Title: PROCESS DEPENDING ON PLASMA DISCHARGES SUSTAINED BY
INDUCTIVE COUPLING

**DECLARATION OF DAVID B. GRAVES IN SUPPORT OF PETITION
FOR *INTER PARTES* REVIEW OF U.S. PATENT NO. 6,017,221
UNDER 35 U.S.C. §§ 311-319 AND 37 C.F.R. §§ 42.1-.80, 42.100-.123**

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